

**RAW MATERIAL FOR CHEMICAL VAPOR DEPOSITION AND METHOD FOR PRODUCING THIN FILM USING THE SAME**

Patent Number: JP2002069641  
Publication date: 2002-03-08  
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Requested Patent: JP2002069641  
Application Number: JP20000349622 20001116  
Priority Number(s):  
IPC Classification: C23C16/18; C07C49/92; C07F7/00; C07F7/28  
EC Classification:  
Equivalents:

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**Abstract**

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**PROBLEM TO BE SOLVED:** To obtain a raw material including group 4 elements such as titanium, zirconium and hafnium suitable for producing a thin film by a CVD method, and also provide a method for producing the thin film using the material.

**SOLUTION:** The raw material for chemical vapor deposition includes a metallic compound expressed by general formula (I) (wherein, M is titanium, zirconium or hafnium, R1, R2 and R5 are each independently an alkyl group which may include one or two oxygen atoms in a 1-8C chain; R3 and R4 are each independently H or a 1-4C alkyl group; A is a 1-4C alkylene group; and (n) is 0, 1 or 3 when M is titanium and 0, 1, 2 or 3 when M is zirconium or hafnium).

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